AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the present application.

Listing of Claims:

1. (**Currently Amended**) An abrasive for metal comprising an oxidizing agent, water and a polymer particle having a functional group that traps a metal ion, wherein the functional group that traps a metal ion is ~~at least one selected from the group consisting of -OH, -COOM, >C=O, -O-, -COOR, -CONH$_2$, -NO, -NO$_2$, >N-O, -SO$_3$M, -PHO(OM), -PO(OM)$_2$, -AsO(OM)$_2$, -N=N-, >C=N-, >C=N-OH, >C=NH, -SCN, -SH, -S-, >C=S, -COSM, -CSSM, -CSNH$_2$, -NCS, >P-, >As-, -SeH, >S=Se, -CSeSeM, amino alcohol, aminophosphonic acid and~~ iminodiacetic ~~acid, wherein M represents a hydrogen, an alkali metal, an alkaline earth metal or an ammonium group and R represents a hydrocarbon.~~ acid.

2-3. (**Canceled**)

4. (**Original**) The abrasive for metal according to claim 1, wherein the particle having a functional group is a particle comprising an ion exchange resin.

5. (**Previously Presented**) The abrasive for metal according to claim 1, wherein the particle having a functional group that traps a metal ion is a particle comprising an ion exchange resin, and the average particle diameter of the particle is 1.0 μm or less.

6. (**Original**) The abrasive for metal according to claim 1, wherein the particle having a functional group is a particle comprising a chelate resin.

7. (**Original**) The abrasive for metal according to claim 1, wherein the particle having a functional group is a particle comprising a chelate resin, and the average particle diameter of the particle is 1.0 μm or less.

8. (**Original**) A process for producing the abrasive for metal according to claim 5, wherein the process comprises wet-milling an ion exchange resin.

9. (**Previously Presented**) A process for producing the abrasive for metal according to claim 5, wherein the process comprises dry-milling and then wet-milling an ion exchange resin.

10. (**Original**) The process for producing the abrasive for metal according to claim 7, wherein the process comprises wet-milling chelate resin.

11. (**Previously Presented**) The abrasive for metal according to claim 1, wherein the metal is copper or copper alloy.

12. (**Original**) A polishing composition for metal comprising an abrasive for metal according to claim 1, an oxidizing agent and water.

13. (**Previously Presented**) The polishing composition for metal according to claim 12, wherein the metal is copper or copper alloy.

14. (**Original**) The polishing composition for metal according to claim 12, wherein the oxidizing agent is hydrogen peroxide.

15. (**Original**) The polishing composition for metal according to claim 12, wherein the composition further comprises at least one selected from the group consisting of a spherical particle, benzotriazole and a benzotriazole derivative.

16. (**Original**) A process for polishing a metal by chemical mechanical polishing, wherein the process is conducted by using the polishing composition for metal according to claim 12.

17. (**Previously Presented**) The process according to claim 16, wherein the metal is copper or copper alloy.

18. (**Previously Presented**) The abrasive for metal according to claim 1, wherein said particle having a functional group is a particle comprising a cation exchange resin.

19. (**Previously Presented**) The abrasive for metal according to claim 1, wherein said particle having a functional group is a particle comprising an anion exchange resin.